CLAIMS

[Claim 1] A polishing liquid set comprising a polymer composition and a liquid, wherein

the polymer composition contains a polymer and an aqueous medium,

the polymer has

a first structural unit derived from at least one styrenic compound selected from the group consisting of styrene and styrene derivatives and

a second structural unit derived from at least one methacrylic acid compound selected from the group consisting of methacrylic acid and its salts,

a weight-average molecular weight of the polymer is 3000 to 500000,

a content of the first structural unit is more than 0 mol% and 38 mol% or less in the polymer,

a content of the second structural unit is 60 to 90 mol% in the polymer,

a content of the polymer is 0.010 to 30 mass% in the polymer composition, and

the liquid contains abrasive grains and an aqueous medium.

[Claim 2] The polishing liquid set according to claim 1, wherein the first structural unit includes a structural unit derived from styrene.

[Claim 3] The polishing liquid set according to claim 1 or 2, wherein a converted total amount of carboxyl groups and carboxylate groups is 6.7×10^{-3} mol/g or more in the polymer, and the converted total amount is calculated by replacing carboxylate groups in the polymer

with carboxyl groups.

[Claim 4] The polishing liquid set according to any one of claims 1 to 3, wherein the abrasive grains contain at least one selected from the group consisting of cerium oxides, silicon oxides, aluminum oxides, zirconium oxides, and yttrium oxides.

[Claim 5] The polishing liquid set according to any one of claims 1 to 4, wherein the abrasive grains contain cerium oxides.

[Claim 6] A method for producing a polishing liquid, comprising a step of mixing the polymer composition and the liquid of the polishing liquid set according to any one of claims 1 to 5.

[Claim 7] A polishing liquid comprising abrasive grains, a polymer, and an aqueous medium, wherein

the polymer has a first structural unit derived from at least one styrenic compound selected from the group consisting of styrene and styrene derivatives and a second structural unit derived from at least one methacrylic acid compound selected from the group consisting of methacrylic acid and its salts,

a weight-average molecular weight of the polymer is 3000 to 500000,

a content of the first structural unit is more than 0 mol% and 38 mol% or less in the polymer,

a content of the second structural unit is 60 to 90 mol% in the polymer, and

a content of the polymer is 0.01 to 10 mass%.

[Claim 8] The polishing liquid according to claim 7, wherein the first structural unit includes a structural unit derived from styrene.

[Claim 9] The polishing liquid according to claim 7 or 8, wherein a converted total amount of carboxyl groups and carboxylate groups is 6.7×10^{-3} mol/g or more in the polymer, and the converted total amount is calculated by replacing carboxylate groups in the polymer with carboxyl groups.

[Claim 10] The polishing liquid according to any one of claims 7 to 9, wherein the abrasive grains contain at least one selected from the group consisting of cerium oxides, silicon oxides, aluminum oxides, zirconium oxides, and yttrium oxides.

[Claim 11] The polishing liquid according to any one of claims 7 to 10, wherein the abrasive grains contain cerium oxides.

[Claim 12] A polishing method comprising a step of polishing a surface to be polished using the polishing liquid according to any one of claims 7 to 11.